CAPACITOR TECHNOLOGY

CAP-M

Processes

Al on polyprophylene

Process 1

Substrate:	(B) OPP
Layer:	Al
Substrate thickness [µm]:	3.5
Substrate length [m]:	Approx. 30.000
Substrate width [mm]:	620
Metallised width [mm]:	600
Process speed [m/s]:	Approx. 9.0
Resistance – active area [Ω/□]:	2.0
Layer uniformity [Ω/□]:	± 0.2

Al on polyethylenterephthalat

Process 2

Substrate:	PET
Layer:	Al
Substrate thickness [µm]:	2.0
Substrate length [m]:	Approx. 10.000
Substrate width [mm]:	500
Metallised width [mm]:	490
Process speed [m/s]:	Approx. 6.0
Resistance – active area [Ω/□]:	1.0
Layer uniformity [Ω/□]:	± 0.1